

Notice of References Cited

Application/Control No.

10/032,649

Applicant(s)/Patent Under
Reexamination
WEISS ET AL.

Examiner

Kripa Sagar

Art Unit

1756

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*	Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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K	US-			
L	US-			
M	US-			

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*	Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
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Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.